

IN THE SPECIFICATION

Please replace the Abstract with the following rewritten Abstract:

A composition for forming a silicon-aluminum film, containing a silicon compound and an aluminum compound. The silicon-aluminum film is obtained by forming a coating film of the above composition and treating it with heat and/or light. [

] The silicon-aluminum film can easily be formed from the above composition by the above method at a low cost without requiring an expensive vacuum apparatus or high-frequency wave generator.

Please replace the paragraph beginning on page 5, line 4, with the following rewritten paragraph:

As illustrative examples of these compounds, the halogenosilane compounds include tetrachlorosilane, tetrabromosilane, hexachlorodisilane, hexabromodisilane, octachlorotrisilane and octabromotrisilane; the cyclic silane compounds include cyclotrisilane, cyclotetrasilane, cyclopentasilane, silylcyclopentasilane, cyclohexasilane, ~~heptasilane~~ cycloheptasilane and cyclooctasilane; the chain silane compounds include n-pentasilane, iso-pentasilane, neo-pentasilane, n-hexasilane, n-heptasilane, n-octasilane and n-nonasilane; the silane compounds having a spiro structure include 1,1'-bicyclobutasilane, 1,1'-bicyclopentasilane, 1,1'-bicyclohexasilane, 1,1'-bicycloheptasilane, 1,1'-cyclobutasilylcyclopentasilane, 1,1'-cyclobutasilylcyclohexasilane, 1,1'-cyclobutasilylcycloheptasilane, 1,1'-cyclopentasilylcyclohexasilylsilane, 1,1'-cyclopentasilylcycloheptasilane, 1,1'-cyclohexasilylcycloheptasilane, spiro[2,2]pentasilane, spiro[3,3]heptasilane, spiro[4,4]nonasilane, spiro[4,5]decasilane, spiro[4,6]undecasilane,

spiro[5,5]undecasilane, spiro[5,6]undecasilane and spiro[6,6]tridecasilane; and the polycyclic silane compounds include hexasilaprisman and octasilacubane.

Please amend the claims as follows:

Claim 1 (Original): A composition for forming a silicon-aluminum film, comprising a silicon compound and an aluminum compound.

Claim 2 (Original): The composition for forming a silicon-aluminum film according to claim 1, wherein the silicon compound is at least one selected from the group consisting of compounds represented by the following formulas (1) to (4):



wherein X is a hydrogen atom, halogen atom or monovalent organic group and "a" is an integer of 2 or more.



wherein X is as defined in the above formula (1) and "b" is an integer of 3 or more.



wherein X is as defined in the above formula (1) and "c" is an integer of 6 or more.



wherein X is as defined in the above formula (1).

Claim 3 (Original): The composition for forming a silicon-aluminum film according to claim 1, wherein the aluminum compound is at least one selected from the group consisting of a compound represented by the following formula (5) and a complex of an amine compound and aluminum hydride:



wherein Y is a hydrogen atom or monovalent organic group.

Claim 4 (Currently Amended): A method of forming a silicon-aluminum film, comprising the steps of forming a coating film of the composition for forming the silicon-aluminum film ~~of any one of claims 1 to 3~~ according to Claim 1 on a substrate and treating the film with heat and/or light.

Claim 5 (Original): A silicon-aluminum film formed by the method of claim 4.